## **IN THE CLAIMS**

Please amend the claims as follows:

1-16. (Cancelled)

17. (Currently Amended) A method of depositing a material along a diameter of a surface having an edge, a center, and an opposite edge, wherein said method comprises:

rotating said surface;

providing a nozzle configured to generate a dispersed mist from the material;

positioning said nozzle generally over said edge, wherein said step of positioning said nozzle generally over said edge further comprises:

positioning said nozzle over a first point along a circumference of said surface; and

defining said first point to be independent of a rotation of said surface; while rotating said surface, spraying the dispersed mist of said material in a single spraying movement from said nozzle while moving said nozzle in a single direction from the first point to a second point of said circumference; and

stopping motion of said nozzle after said nozzle passes over said center, wherein said step of stopping motion of said nozzle further comprises stopping motion of said nozzle when said nozzle is over said opposite edge, and wherein said step of stopping motion of said nozzle when said nozzle is over said opposite edge further comprises:

stopping motion of said nozzle and stopping spraying over the second point along said circumference; and

defining said diameter with said first point, said center, and said second point.

18-30. (Cancelled)

31. (Previously Presented) The method of claim 17, wherein rotating said surface includes rotating between 500 and 1500 rpm.

AMENDMENT AND RESPONSE UNDER 37 CFR § 1.111

Serial Number: 10/656,745

Filing Date: September 5, 2003

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32. (Previously Presented) The method of claim 31, wherein rotating said surface includes

rotating in a 50% humidity atmosphere.

33. (Previously Presented) The method of claim 32, wherein rotating said surface includes

rotating at 72 degrees F.

34. (Cancelled)

35. (Previously Presented) The method of claim 17, wherein spraying said material from said

nozzle includes dispensing a solution in a fine mist.

36. (Previously Presented) The method of claim 17, wherein spraying said material from said

nozzle includes dispensing in a dispersed and divergent pattern.

37. (Previously Presented) The method of claim 17, wherein spraying said material from said

nozzle includes spraying a liquid comprising an organic solvent.

38. (Previously Presented) The method of claim 17, wherein spraying said material from said

nozzle includes spraying a polymer dielectric.

39. (Currently Amended) A method of depositing a wafer-coating, liquid material along a

diameter of a wafer surface having a circumferential edge and a center, comprising:

rotating the wafer surface;

providing a nozzle configured to generate a dispersed mist from the material;

positioning the nozzle generally over the edge prior to spraying;

while rotating the wafer, beginning a single spraying movement of the wafer-coating

material from the nozzle at a first point on a diameter of the wafer at that is over the edge of the

wafer surface;

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while spraying, moving the nozzle in a single direction from the first point to a second point over an opposing edge of the wafer and the second point on the diameter, over the center point, and to the edge of the wafer surface; and

stopping the single spraying movement at the second point.

- 40. (Previously Presented) The method of claim 39, wherein rotating the wafer surface includes rotating between 500 and 1500 rpm in a 50% humidity atmosphere at 72 degrees F.
- 41. (Previously Presented) The method of claim 40, wherein spraying the wafer-coating material from the nozzle includes spraying a polymer dielectric.